Investigation of InGaN-based red/green micro-light-emitting diodes

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We investigated the performance of InGaN-based red/green micro-light-emitting diodes (μ LEDs) ranging from 98×98 to 17×17 μ m². The average forward voltage at 10 A/cm² was independent of the dimension of μ LEDs. Red μ LEDs exhibited a larger blue-shift of the peak wavelength (~35 nm) and broader full-width at half maximum (\geq 50 nm) at 2 to 50 A/cm² compared to green μ LEDs. We demonstrated that 47×47 μ m² red μ LEDs had an on-wafer external quantum efficiency of 0.36% at the peak wavelength of 626 nm, close to the red primary color defined in the recommendation 2020 standard.

Micro-light-emitting diodes (μ LEDs) have recently gathered considerable interest for next-generation display applications, such as smartphones and watches, augmented reality (AR), and virtual reality (VR) devices [1,2]. The primary colors (red, green, and blue, RGB) are required to be achieved separately to develop full-color displays. InGaN-based blue μ LEDs are the best choice for blue color displays because they have demonstrated remarkable performances, even when the device dimension decreases to 10 μ m or less [3,4].

Two approaches could realize green and red colors. A simple method uses blue or violet μ LEDs to excite color converters, such as phosphors or quantum dots [5,6]. This method can easily integrate RGB colors into matrices on the same substrate [7], yet the color-conversion efficiency of hybrid devices must be improved [8]. Another approach chooses to fabricate red and green μ LEDs using different materials, AlInGaP for red μ LEDs [9] and InGaN for green μ LEDs [10]. This material difference causes a mismatched angular distribution between the red and green μ LEDs [11], leading to a noticeable color shift at different observed angles. Besides, AlGaInP red μ LEDs typically suffer from great efficiency reduction because of the high surface recombination when the device dimensions shrink [12].

Therefore, expanding interest was spent on developing InGaNbased red µLEDs. The major challenge for achieving InGaN-based red µLEDs is the significant reduction of the external quantum efficiency (EQE) owing to high-indium-content in the active region. The large lattice mismatch between the InGaN active region and GaN cladding layers results in many defects in InGaN quantum wells. To reduce the lattice mismatch, partly relaxed InGaN pseudo-substrates were utilized in 50×50 µm² sized red InGaN µLEDs, which were demonstrated with an on-wafer EQE (the output power was measured on a wafer instead of in the integrating sphere) of 0.09% at a current density of 40 A/cm² with a peak emission wavelength of 616 nm [13]. A recent 6×6 µm² InGaN red µLED was realized on porous GaN pseudo-substrates, and it achieved a record on-wafer EQE of 0.2% at a current density of 10 A/cm² with a peak emission wavelength of 632 nm [14]. To our knowledge, this on-wafer EQE is the highest reported value for InGaN red µLEDs. Recently, a high wall-plug efficiency (WPE) of 16.8% at 621 nm was obtained at 0.8 A/cm² for 1×1 mm² InGaN-based LEDs [15]. This WPE value was the highest for standard InGaN red LEDs. Our group first developed a high-temperature growth technique for high-indium-content InGaN layers [16,17], and then employed strain engineering strategies from Ga_2O_3 substrates [18] and GaN templates [19] to active region structures [20]. We also improved the electrical and optical properties of InGaN LEDs in device design and fabrication [21,22]. Since InGaN-based green and red µLEDs do not perform as well as blue µLEDs, investigation of green and red µLEDs is crucial to identify the direction for future improvements.

This work examined the performances of InGaN-based red/green μ LEDs ranging from 98×98 to 17×17 μ m². Current-voltage (*I-V*) curves were used to estimate the forward voltages and reverse leakage currents. We investigated the EL characteristics of red/green μ LEDs at different current densities, including the EL peak wavelength, full-width at half maximum (FWHM), on-wafer EQE and color gamut. Finally, we also evaluated the temperature dependence of EL emission for red/green μ LEDs.

InGaN-based red LED epitaxial wafers were grown on c-plane patterned sapphire substrates by metalorganic vapor-phase epitaxy (MOVPE) in a single-wafer horizontal reactor at 100 kPa [16]. The epitaxial structures of the InGaN-based red LEDs were reported in our previous work [19]. Indium tin oxide (ITO) films were deposited as a transparent conductive layer and subjected to two-step annealing to form ohmic contacts with p-GaN [21]. The µLED mesas ranging from 98×98 to 17×17 μ m² were patterned by standard photolithography and then etched through the ITO layer and InGaN active region by inductively coupled plasma (ICP) to expose the ntype layer. A SiO₂ isolated layer was then deposited using plasmaenhanced chemical vapor deposition (PECVD). Finally, we opened the SiO₂ windows on the ITO and n-type layers by ICP etching and deposited Cr/Pt/Au (50 nm/200 nm/200 nm) as n-type and p-type contact pads. All the red µLEDs with different dimensions were fabricated on the same wafer. In the case of InGaN-based green μ LEDs, we used commercial epitaxial wafers on *c*-plane patterned sapphire substrates and performed the same fabrication process.

The electrical pumping of red and green μ LEDs was carried out at a probe station using a semiconductor parameter analyzer. The EL characteristics were measured under direct current operation ranging from 295K (room temperature, RT) to 373K. The temperatures were measured from the sample-holding stage of the probe station. We also calculated the on-wafer EQE by the output power collected from the top side of the μ LEDs.

Figure 1(a) shows the absolute current density-voltage (|J|-V) curves for InGaN-based red µLEDs with the dimension from 98×98 to 17×17 µm². The absolute current density was on a logarithmic

scale. At the forward voltage, the |J|-V curves were identical for all red µLEDs with different dimensions. The turn-on voltage, which was regarded as the transition point of the two linear parts in the semi-logarithmic scale in Figure 1(a), was between 2.5 and 3 V. However, at the reverse voltage, the absolute current density increased with decreasing the dimension of red µLEDs. This behavior was opposite from our previous work [22] for red LEDs in different chip sizes larger than 100×100 µm². We attributed this larger reverse leakage current for 17×17 µm² µLEDs to the sidewall damages after ICP etching. Previous work [3] has shown that sidewall damage after ICP etching can be removed by suitable surface treatments.



FIG. 1. (a) Absolute current density of red μ LEDs with the mesa area of 17×17 μ m², 47×47 μ m², 98×98 μ m² at different bias voltages. (b) Averaged forward voltages of five red and green μ LEDs at 10 A/cm².

We also compared the forward voltage of red and green μ LEDs at 10 A/cm². The average forward voltage was approximately 3.0 and 2.4 V for red and green μ LEDs, respectively. Generally, the red μ LEDs were expected to exhibit a lower forward voltage since the energy bandgap of the red active region was narrower. However, because we adopted AlN/AlGaN as the barrier layers to compensate the strain in InGaN red quantum wells [23], a higher bias voltage was required for carriers to pass through the whole active region. Therefore, our red μ LEDs exhibited a higher forward voltage for both red and green μ LEDs was independent of the μ LED dimension, demonstrating good current spreading and low series resistance in our μ LEDs [24].



FIG. 2. (a) EL emission images of red and green μ LEDs with the mesa area of 17×17 μ m², 47×47 μ m², 98×98 μ m². (b) Normalized EL spectra of red and green μ LEDs with an area of 47×47 μ m². The current density was 4 A/cm².

We captured the emission patterns of red and green μ LEDs at 4 A/cm², as shown in Figure 2(a). Clearly, most device area of the red and green μ LEDs from 98×98 to 17×17 μ m² exhibited uniform luminescence although some bright spots were observed in the red μ LEDs. The common red LEDs with a large mesa area in our previous work [22] displayed many dark points in the emission patterns. These dark points were usually corresponding to the defects in the InGaN red active region. However, these dark points were not found in the red μ LEDs because of much smaller mesa areas, demonstrating high crystal quality for our red μ LEDs. Figure 2(b) shows the typical EL spectra for 47×47 μ m² red and green μ LEDs at

FWHM were investigated from 2 to 50 A/cm² at RT. Figures 3(a) and 3(b) shows the average peak wavelength and FWHM for red and green μ LEDs with the dimension of 47×47 μ m² and 98×98 μ m². We measured three chips and calculated the average values to represent the typical results. From Figures 3(a) and 3(b), we discovered that the peak wavelength and FWHM behaviors at different current densities were independent of the dimensions of red and green μ LEDs. The similar behaviors reflected that the polarization field and the indium fluctuation in InGaN red or green active regions were identical despite of the shrinking of the μ LED sizes.

4 A/cm². Two small additional peaks at around 550 nm and 690 nm

Red uLEDs exhibited a much larger blue-shift (around 35 nm) compared to green uLEDs (around 6 nm) at 2 to 50 A/cm². The larger blue-shift of the peak wavelength originated from the stronger OCSE existing in the red InGaN active region. The average FWHM dropped to the minimum values of 50 nm for red µLEDs and 27 nm for green µLEDs at low current densities, respectively. This behavior was related to the saturation of the emission from deep localized states in the InGaN-based red and green active region [25]. After the minimum value, the average FWHM of red µLEDs increased with the current densities slightly. Our previous work [22] found that the reason for the broad FWHMs was the heat generation in devices under high direct current injection. The heat was usually generated around the defect area because defects contributed as thermal resisters [26]. However, green µLEDs did not show significant broaden FWHMs at high current densities. We presumed that the thermal effect could be ignored due to the low defect densities in the InGaN green active region.



FIG. 3. (a) Average peak wavelength, (b) average FWHM, and (c) average on-wafer EQE of three red and green μ LEDs with the area of 47×47 μ m², 98×98 μ m² at different current densities. (d) CIE diagram of a red and green μ LED with the area of 47×47 μ m² at different current densities. The stars are the primary red and green colors defined in Rec. 2020.

We also calculated the average on-wafer EQEs for red and green μ LEDs at different current densities from 2 to 50 A/cm², as shown in Figure 3(c). The on-wafer EQE first rose to the maximum values at the peak current density of 6 A/cm² and 8 A/cm² for 98×98 μ m² and 47×47 μ m² green μ LEDs, respectively. And then, it suffered from an efficiency droop and dropped quickly with the increasing current

densities. The maximum on-wafer EQE was 3.7(1)% and 3.5(5)% for $98 \times 98 \ \mu\text{m}^2$ and $47 \times 47 \ \mu\text{m}^2$ green μLEDs , respectively. From these data, we concluded that the peak current density would increase while the maximum on-wafer EQE would decrease for green μLEDs when the device dimension shrank. The results were mostly caused by surface recombination at the active region edges, as explained in previous reports [27,28].

The red μ LEDs behaved in a similar way at the low current densities in Figure 3(c). The average on-wafer EQE rose to the maximum values of 0.62% and 0.56% at the peak current density of 20 A/cm² for 98×98 µm² and 47×47 µm² red µLEDs, respectively. A slight reduction of the maximum on-wafer EQE for different device dimensions was also observed in red µLEDs. However, unlike green µLEDs, red µLEDs did not show an obvious efficiency droop (<7%) at the current density up to 50 A/cm². We assumed that this phenomenon was due to higher dislocation densities in red µLEDs than green µLEDs [29]. The efficiency droop of our red µLEDs was better than the previous work [14], which was assumed to be owing to better crystal quality and carrier confinement by AlN/AlGaN barriers in our red active region.

Furthermore, we measured the absolute output power of 47×47 µm² green µLEDs in the integrating sphere and determined the calibration factor for an on-wafer light output measurement *vs.* absolute output measurement in the integrating sphere. This calibration method was also used in other works [13,14]. Green µLEDs in this work were not encapsulated with resin when measured in the integrating sphere. From Figures 3(a) and 3(c), the average onwafer EQE of 47×47 µm² red µLEDs was 0.36% at the peak wavelength of 626 nm at 4 A/cm². Based on the calibration factor, an absolute EQE of approximately 0.87% could be expected from our 47×47 µm² red µLEDs when measured in the integrating sphere. This estimated EQE value exceeds the reported one (>0.6%) calculated by the same method in the previous work [14].

The CIE 1931 positions for red and green μ LEDs at 2 to 50 A/cm² are shown in Figure 3(d). These positions determined the physiologically perceived colors in human color vision. According to the recommendation (Rec.) 2020 standard, the primary red and green colors were located at the coordinates of (0.708, 0.292) and (0.17, 0.797), respectively. They were marked as red and green stars as reference points in Figure 3(d). Clearly, a small gap existed between the coordinates of green μ LEDs and the defined green color in Rec. 2020. This gap illustrated that the color saturation of green μ LEDs was insufficient, which was originated from broad FWHM of InGaN-based green μ LEDs and the reference point of green color in Rec. 2020 remained almost constant with the current density.

However, red μ LEDs exhibited different movements relative to green μ LEDs. At the low current density, the position was close to the reference point of red color in Rec. 2020. When the current density was increased, the coordinate position shifted farther away from the reference point. As a result, the color gamut area coverage would be reduced when red μ LEDs operated at higher current densities. Since this position shift of red μ LEDs is originated from a large blue-shift of the peak wavelength, eliminating or reducing the QCSE in InGaN red active region is necessary to decrease this shift. Another approach is to fabricate longer peak wavelengths of red μ LEDs, which could guarantee the gamut area coverage even at high current densities. Although the FWHM of red μ LEDs was much larger than that of green μ LEDs, the values of 50-52 nm seemed to be acceptable because all positions were located at the edge of the color space in the CIE 1931 diagram.

Finally, we investigated the temperature dependence of the EL integrated intensity and peak wavelength for the $47 \times 47 \ \mu m^2$ red and green $\mu LEDs$, as shown in Figures 4(a) and 4(b), respectively. The

EL intensities of red and green μ LEDs dropped with temperature, which is usually called the thermal droop [30]. From the fitting dot lines in Figure 4(a), the characteristic temperatures were obtained as 50K and 411K at 10 A/cm² for red and green μ LEDs, respectively. The smaller characteristic temperature for red μ LEDs indicated that the InGaN red active region has many Shockley-Read-Hall (SRH) recombination centers [30], which are related to the defect density and become more effective with temperature.

Figure 4(b) shows that the red and green μ LEDs exhibit the redshift of the peak wavelength with increasing temperature. The redshift is caused by the shrinking of the InGaN bandgap. The redshift coefficients of the peak wavelength was 0.126 nmK⁻¹ and 0.038 nmK⁻¹ for red and green μ LEDs, respectively. The redshift coefficient of InGaN red μ LEDs was slightly smaller than that of AlInGaP red LEDs [31,32], indicating smaller temperature dependence of InGaN materials. However, InGaN red μ LEDs show the larger coefficient to more SRH recombination centers in InGaN red active region. The SRH recombination became effective and led to less carrier density for radiative recombination in the active region with temperature. As a result, the red active region suffered from more QCSE and had a larger redshift of the peak wavelength.



Figure 4. (a) Normalized intensity, (b) peak wavelength, and (c) CIE diagram of $47 \times 47 \ \mu m^2$ red and green $\mu LEDs$ operated at different temperatures at 10 A/cm².

To estimate the influence of temperature in the color space, we plotted the temperature dependence of the color coordinates in the CIE 1931 diagram (Figure 4(c)). The movements of red and green μ LEDs are marked with arrows in Figure 4(c). The green μ LEDs moved away from the reference point of green color in Rec. 2020 (green star in Figure 4(c)) with increasing temperature. Therefore, the gamut area coverage would be reduced due to this movement of green μ LEDs. On the contrary, red μ LEDs moved towards the reference point of red color in Rec. 2020 (red star in Figure 4(c)) with temperature. Although the movement of red μ LEDs led to the hue variation, the gamut area coverage could be increased.

In summary, we investigated the performance of InGaN-based red/green μ LEDs ranging from 98×98 to 17×17 μ m². The average forward voltage at 10 A/cm² was independent of the dimension of μ LEDs. But the reverse leakage currents of red μ LEDs increased with the reduction of device dimension. A large blue-shift of the peak wavelength (~35 nm) and a broad FWHM (≥50 nm) at 2 to 50 A/cm² were observed in red μ LEDs. An on-wafer EQE of 0.36% (corresponding to an expected absolute EQE of 0.87%) at the peak wavelength of 626 nm at 4 A/cm² was achieved from the 47×47 μ m²

red μ LEDs. Considering the positions in the CIE 1931 diagram, we recommend suppressing the peak wavelength blue-shift for the red μ LEDs and making FWHM narrower for the green μ LEDs to improve the color quality and stability. InGaN red μ LEDs suffer from a severe thermal droop compared to green μ LEDs, but the

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coordinates of the red μ LEDs in the CIE 1931 diagram move towards the primary red color (Rec. 2020) with temperature. This opposite movement to the green μ LEDs helps to increase the gamut area coverage in the color space.

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